

U-PUR

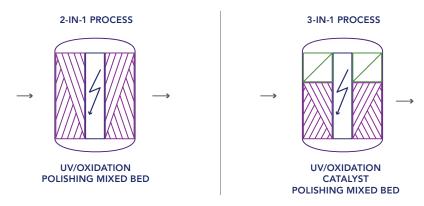
The U-PUR is designed and manufactured to meet challenging applications such as semiconductors, medical, pharmaceutical and all other industrial applications that exclusively require Ultrapure Water (UPW).

Conventional polishing systems include standalone UV's constructed of electro-polished stainless steel. The combination of the UV reactor and the polishing resin vessel enables the elimination of a potential source of contamination (oxidizable particles) within the polishing system.



This unique metal-free reactor also combines multiple UPW polishing steps for the removal of TOC and H₂O₂ traces. The 2-in-1 process step can easily be upgraded at any time in 3-in-1 by adding a catalyst resin without further modification.

INNOVATIVE POLISHING PROCESS



TECHNICAL SPECIFICATIONS

U-PUR		08	40
VESSEL DIAMETER	mm (inch)	460 (18.1)	1′000 (39.4)
HEIGHT (MAX.)	mm (inch)	2′500 (98.4)	3′300 (130)
TREATMENT CAPACITY	m³/h (gpm)	3 10 (13 44)	15 50 (65 220)
SERVICE PRESSURE (MAX.)	bar (psi)	6 (87)	
NUMBER OF UV LAMPS (185+254)		3	15
UV POWER	kW	1	5
ION EXCHANGE RESINS			
MIXED BED OvivUP™ – M020	l (gal)	100 (26.4)	500 (132)
CATALYST CatOX	l (gal)	60 (15.9)	300 (79.2)

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Ovivo is a global leader in water solutions for the semiconductor industry and the only water company which had been a member of the former F450C consortium.

ovivowater.com

KEY FEATURES



STANDALONE SOLUTION

All process functions managed locally





ULTRAPURE WATER COMPOSITION

TOC < 1ppb H₂O₂ < 1 ppb



LOW PRESSURE DROP

Less friction, simplified process



ENERGY EFFICIENT

Power consumption optimization



USER-FRIENDLY

Easy to operate, designed to facilitate servicing



Less engineering, more flexibility

